

IN THE DRAWINGS:

Attached are formal drawings to replace Sheet 5 and Sheet 6.

IN THE SPECIFICATION:

On page 5, line 12 please replace the paragraph with the following two new paragraphs.

FIG. 8a. Schematic cross-sectional view of a horizontal embodiment of a single-wafer megasonic cleaning apparatus having a pair of transducers mounted on either side of a substrate in accordance with the present invention.

FIG. 8b. Schematic top view of the horizontal embodiment of FIG. 8a.

On page 10, last line to page 11, line 11, please replace the paragraph with the following new paragraph.

In a horizontal implementation of the invention lower array of transducers **210a'** are held in container **206**, as illustrated in **FIGS. 8a, 8b**. Lower array of transducers **210a'** have openings **211** between some of the individual transducers of the array for the entrance of fluid **220** into container **206**. Substrate **90** is held above transducers **210a'** with substrate holders **208**. Fluid flows past both sides of substrate **90** before overflowing container **206** at overflows **260**. Upper array of transducers **210b'** can be brought into position with transducer loading arm **212** once substrate **90** has been loaded on holders **208**. This embodiment allows more control over spacing between substrate and transducers than the embodiment of **FIG. 7**. Spacing between the bottom surface of substrate **90** and lower array of transducers **210a'** is fixed by holders **208**. Spacing of top surface from upper array of transducers **210b'** can be controlled by adjusting height of upper array **210b'** to accommodate differences in substrate thickness.